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(54) CHEMICAL AMPLIFICATION TYPE POSITIVE TYPE RESIST COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To improve adhesiveness to a substrate by incorporating a resin having a residue of optionally alkyl subst'd. butyrolactone and an acid generating agent.

SOLUTION: This resist compsn. contains a resin usually obtd. by (co) polymerizing a compd. having an ethylenic unsatd. bond and an acid generating agent. It is preferable that the resin does not have an arom. ring but has alicyclic rings. The resin has a residue of optionally alkyl subst'd. butyrolactone. The alkyl is about 1-4C alkyl such as methyl, ethyl or propyl. The acid generating agent generates an acid when it is degraded by the action of radiation such as light or electron beams on the agent or the resist compsn. contg. the agent. The agent is, e.g. an onium salt compd. or an org. halogen compd.

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